

# **EUV Lithography: present and future**

Mark van de Kerkhof, Vadim Banine

mark.van.de.kerkhof-msd@asml.com

*ASML Netherlands B.V., De Run 6501, 5504 DR Veldhoven, The Netherlands*

EUV Lithography has established itself as the technology of choice for High-Volume Manufacturing (HVM) of 5 nm node and beyond, ensuring that Moore's law will continue for the coming years. We will discuss the performance and remaining challenges of the current EUV scanners and the related critical technologies such as reticles, resists and metrology.

We will also discuss the upcoming next generation of EUV scanners, with increased NA and improved resolution.